



## Correction to: XUV laser mass spectrometry for nano-scale 3D elemental profiling of functional thin films

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**Correction to: Applied Physics A (2020) 126:230**  
<https://doi.org/10.1007/s00339-020-3381-3>

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In the original article, one of the texts was missing in the Acknowledgment section.

It should read as follows:

**Acknowledgements** The authors acknowledge Prof. J. J. Rocca and Prof. C. S. Menoni (Colorado State University) for the original proof-of-principle of the Argon capillary discharge laser (now operative in our laboratory) on our own samples. The research was exclusively funded internally at Empa by the two laboratory involved, as explorative project on instrumentation R&D. XUV TOF was operated by Lydia Rush, graduate student in the Department of Electrical and

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The original article can be found online at <https://doi.org/10.1007/s00339-020-3381-3>.

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